ASML TWINSCAN XT:1400F
193nm (ArF) Scanner
Lithography Equipment

Equipment details:
Currently Configured for: 300mm
Asset HDD not included
• Cymer XLA-165 45 W. 4kHz laser
• 4 FOUP Loadports
• Projection Lens The Starlith Aerial E illumination system Quasar illumination module Beam Delivery syst
• Alignment System
o Wafer alignment using ATHENA
o Reticle BLUE alignment
o ATHENA narrow marks
o TOP 1 and TOP 2
• Lot streaming Scanning stages Wafer handling Exposure chucks Lot overhead reduction
• Focus control and field by field leveling Focus Spot Monitoring CD-FEDC LS MATCH2
• Reticle shape correction
• System calibration and image quality control in-situ metrology (ILIAS SAMOS) Lithoguide Pupicom Dos
• UNIX/SUN Architecture for user interface
• Reticle management reticle error compensation
• DOE Low Sigma 193
• Aux Port 300mm FOUP/25 wafer
• IRIS for Twinscan 6 Inch
• Integrated reticle library